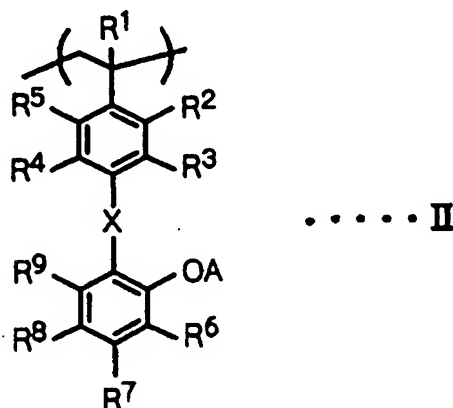


ABSTRACT

There is disclosed a photosensitive resin composition for interlayer insulating films, surface protection films or the like, which exhibits excellent resolution and can be developed with an aqueous alkaline solution. The

5 photosensitive resin composition is prepared using a polymer at least having a constitutional repeating unit represented by general formula II:



wherein R¹ represents hydrogen atom or methyl group; R² to R⁹ independently represent hydrogen atom, halogen atom or alkyl group having
 10 1 to 4 carbon atoms; X represents -CH=N-, -CONH-, -(CH₂)_n-CH=N- or -(CH₂)_n-CONH- and the N atom in X is bonded to a carbon atom in the benzene ring having AO- at an o-position; A represents hydrogen atom or a group being decomposed by an acid; and n represents a positive integer of 1 to 3.